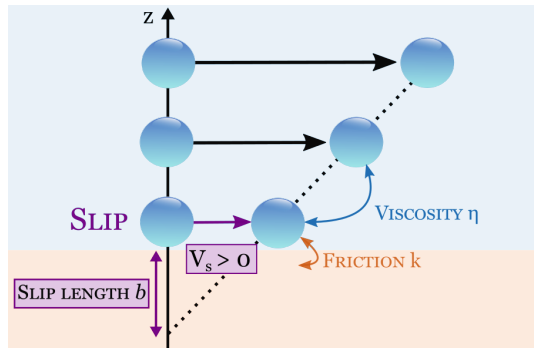


# EFFECT OF TEMPERATURE ON WALL SLIP OF A MODEL FLUID

Suzanne Lafon<sup>1</sup>, Laurent Joly<sup>2</sup>, Samy Merabia<sup>2</sup>, Alexis Chennevière<sup>3</sup>, Frédéric Restagno<sup>1</sup>

<sup>1</sup>Laboratoire de Physique des Solides, Université Paris-Saclay, Orsay ; <sup>2</sup>Institut Lumière-Matière, Université Claude-Bernard, Villeurbanne ; <sup>3</sup>Laboratoire Léon Brillouin, CEA-Saclay

## Wall slip boundary condition



Continuity of stress  $\tau$  at the L/S interface [1]:

$$\tau_{wall} = \eta \frac{\partial v}{\partial z} = k V_s$$

$$b = \frac{\text{viscosity}}{\text{friction}} = \frac{\eta}{k}$$

## Temperature dependency

Viscosity and friction are assumed to be activated processes: [4]

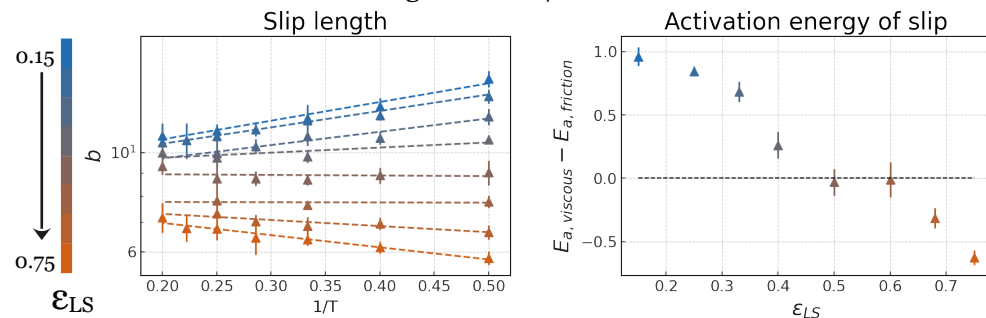
$$\eta = \eta_0 e^{E_{a,viscous}/k_B T}$$

$$k = k_0 e^{E_{a,friction}/k_B T}$$

$$b = \frac{\eta_0}{k_0} e^{(E_{a,viscous} - E_{a,friction})/k_B T}$$

## Results

$b(T)$  can also be described by an activated-like process and its monotony depends on the strength of the L/S interaction.

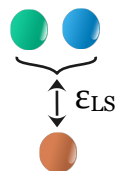


$b$  is in  $\sigma$  units (typically  $3\text{\AA}$ ) and  $T$  is in  $\epsilon_{LL}/k_B$  units.  $T_g$  is around 0.5.

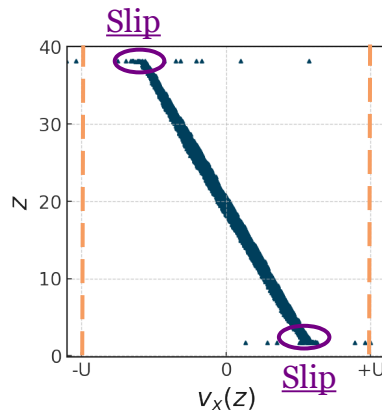
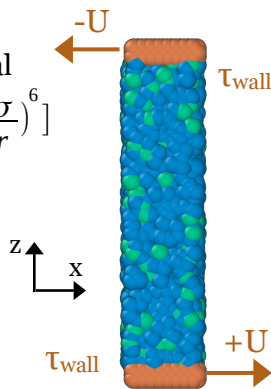
## System and method

We use a Kob-Andersen [2] fluid sheared by two smooth walls [3].

Lennard-Jones interaction potential

$$U(r) = 4 \epsilon_{ij} \left[ \left( \frac{\sigma}{r} \right)^{12} - \left( \frac{\sigma}{r} \right)^6 \right]$$


Variable L/S interaction



## Conclusion

The effect of temperature on slip is not straightforward. For a Kob-Andersen fluid at sufficiently large temperatures, viscosity, friction and slip are activated processes with activation energies  $E_{a,viscous}$ ,  $E_{a,friction}$  and  $E_{a,viscous} - E_{a,friction}$  respectively. Therefore, the monotony of  $b(T)$  depends on the sign of this difference of energies, which is a function of the strength of the L/S interaction.

[1] C. L. Navier, "Mémoire sur les lois du mouvement de fluides" (1823) ; [2] W. Kob & H. C. Andersen, *Phys. Rev. E* **51**, 4626 (1995) ; [3] C. Herrero, G. Tocci, S. Merabia & L. Joly, *Nanoscale* **12**, 20396 (2020) ; [4] M. Hénot, M. Grzelka *et al.*, *Phys. Rev. Lett.* **121**, 177802 (2018)